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KIM et al.(10) **Pub. No.: US 2017/0155074 A1**(43) **Pub. Date: Jun. 1, 2017**(54) **ORGANIC EMITTING DIODE AND
ORGANIC LIGHT EMITTING DIODE
DISPLAY DEVICE INCLUDING THE SAME***H01L 51/56* (2006.01)*H01L 51/52* (2006.01)*H01L 27/32* (2006.01)(71) Applicant: **LG Display Co., Ltd.**, Seoul (KR)(72) Inventors: **Hee-Jin KIM**, Gyeonggi-do (KR);
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Sung-Soo PARK, Gyeonggi-do (KR)(73) Assignee: **LG Display Co., Ltd.**, Seoul (KR)(21) Appl. No.: **15/354,178**(22) Filed: **Nov. 17, 2016**(30) **Foreign Application Priority Data**

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Publication Classification(51) **Int. Cl.***H01L 51/50* (2006.01)*H01L 51/00* (2006.01)(52) **U.S. Cl.**CPC *H01L 51/5076* (2013.01); *H01L 51/5206*(2013.01); *H01L 51/5221* (2013.01); *H01L**51/5004* (2013.01); *H01L 51/5016* (2013.01);*H01L 27/3211* (2013.01); *H01L 27/3244*(2013.01); *H01L 51/56* (2013.01); *H01L**51/0004* (2013.01); *H01L 51/0003* (2013.01);*H01L 2251/552* (2013.01)(57) **ABSTRACT**

The present invention provides an organic emitting diode including a first electrode; a second electrode facing the first electrode; an emitting material layer between the first and second electrodes; and an intervening layer between the emitting material layer and the second electrode and including a base material and an electron injection material, wherein the intervening layer contacts the second electrode.

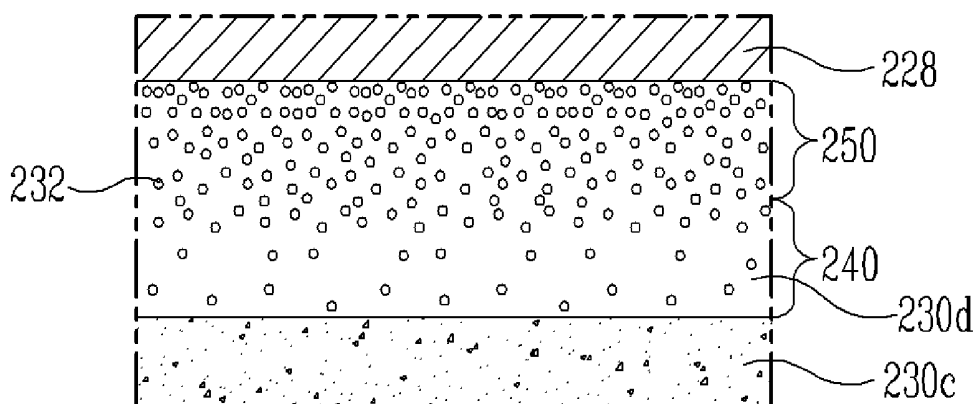


FIG. 1
Related Art

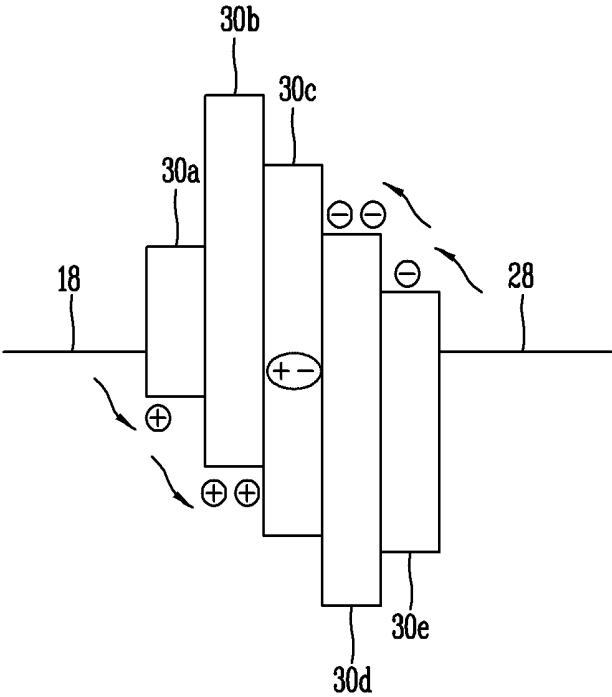


FIG. 2
Related Art

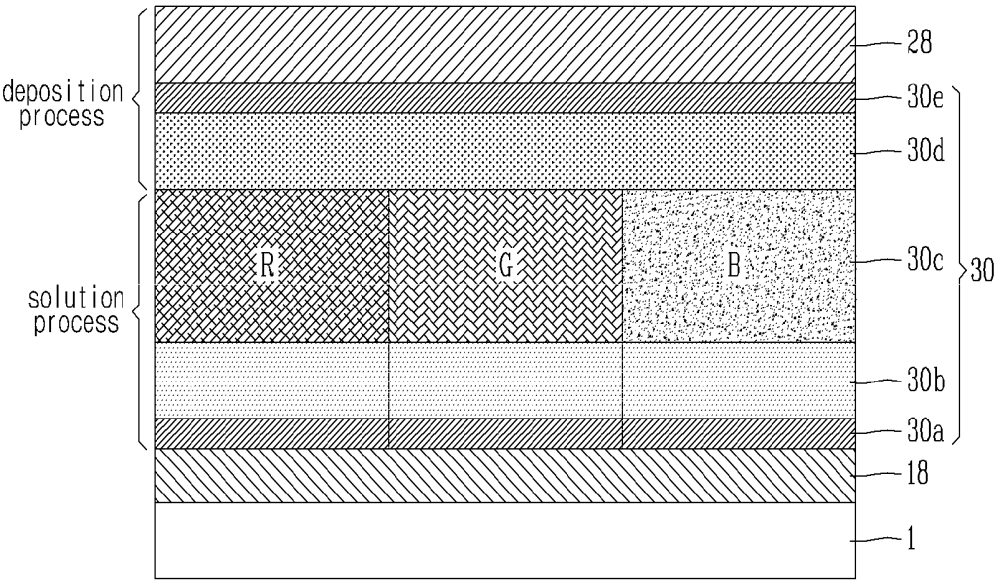


FIG. 3

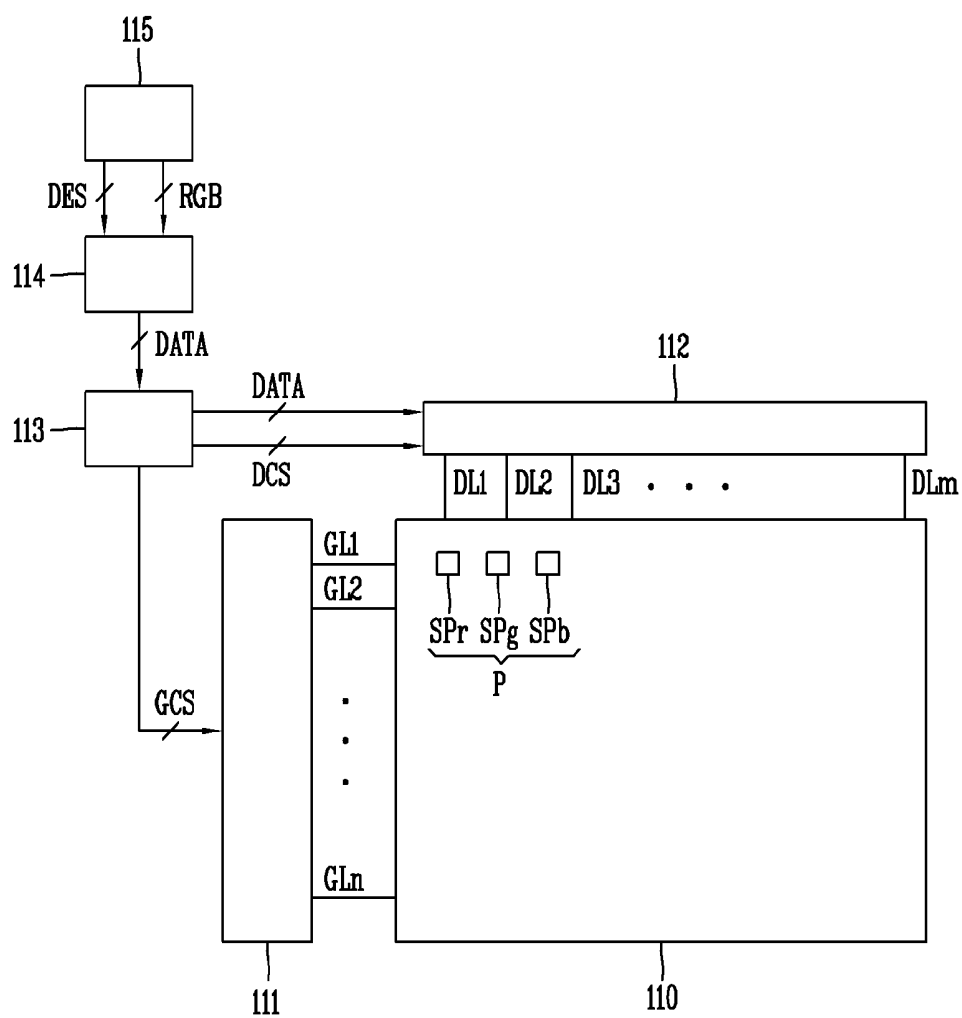


FIG. 4

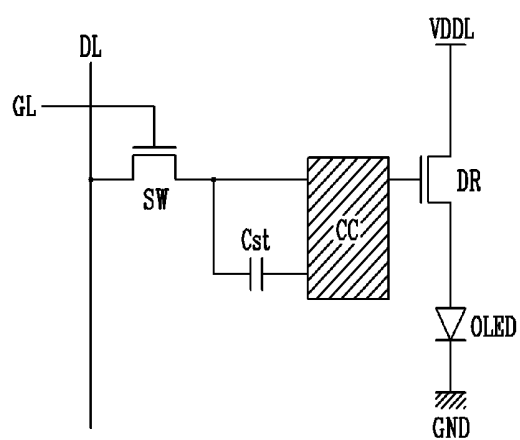


FIG. 5

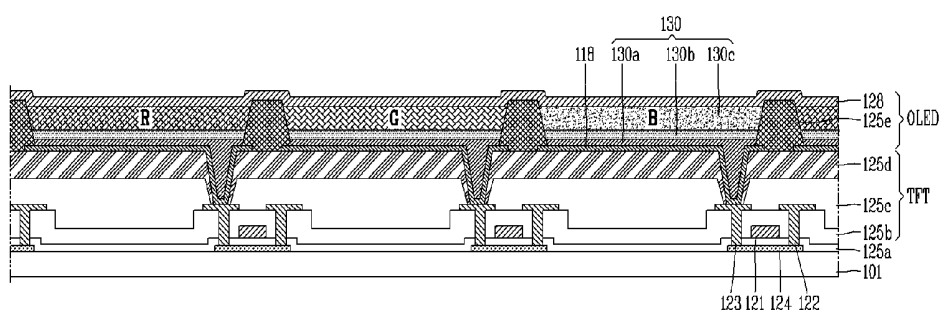


FIG. 6

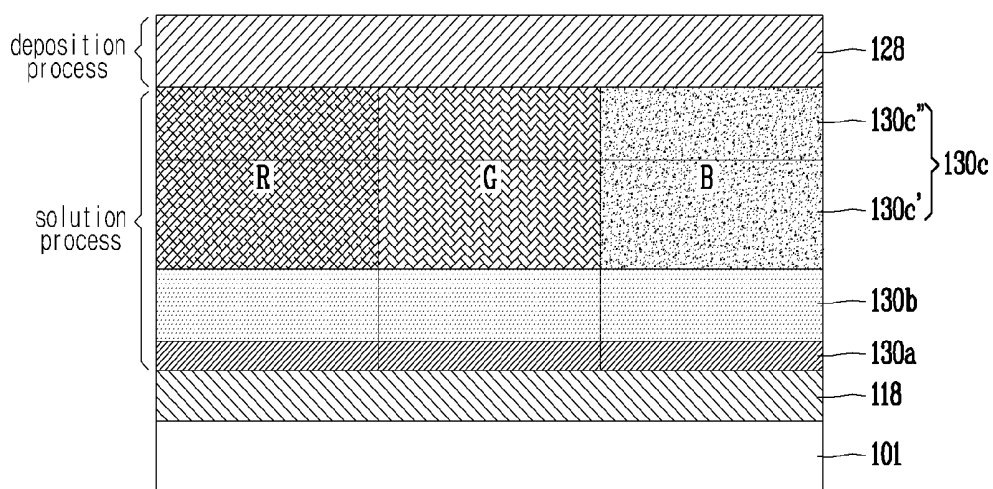


FIG. 7A

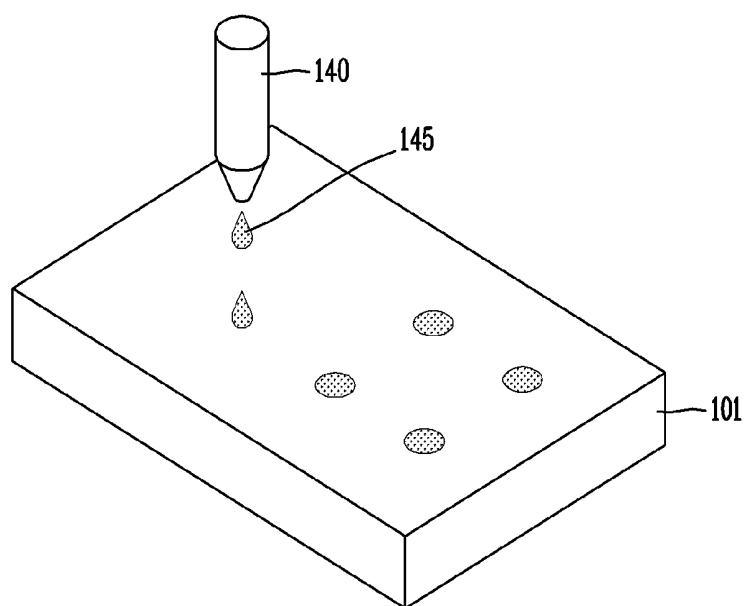


FIG. 7B

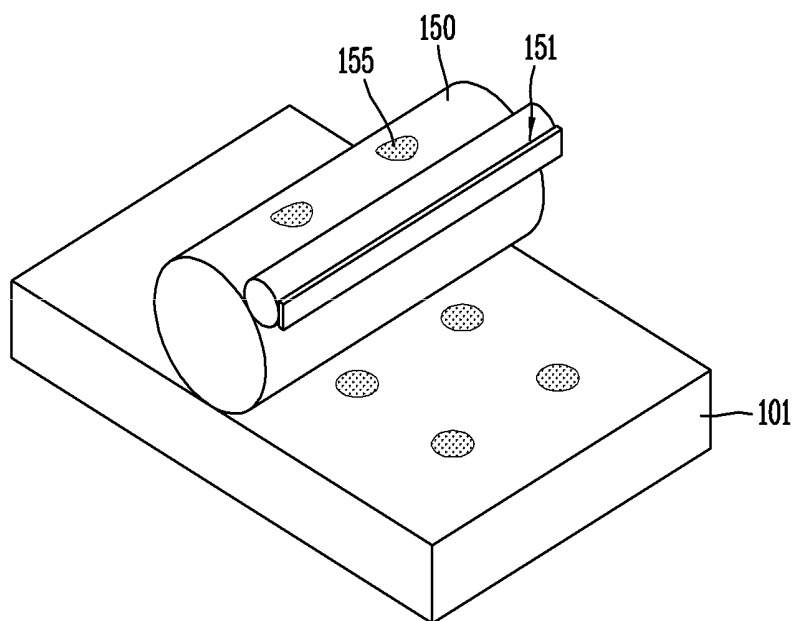


FIG. 8

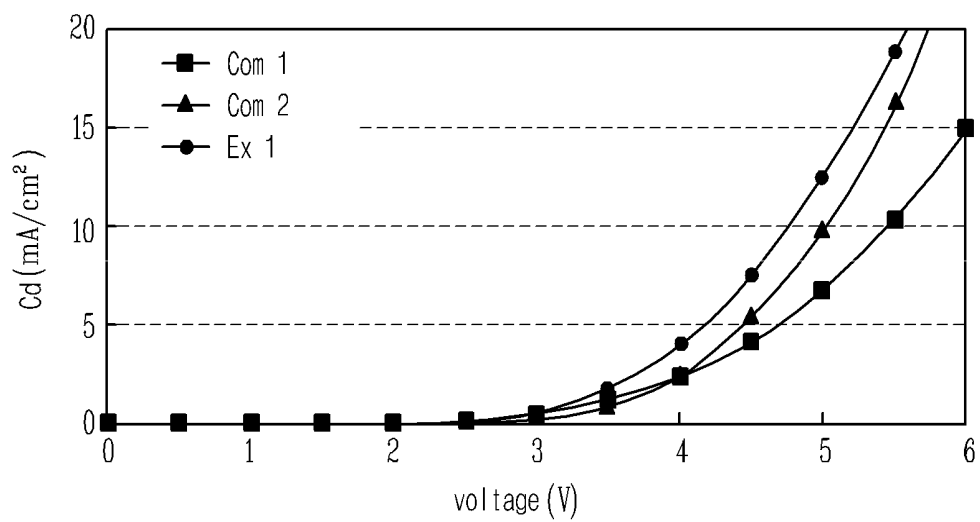


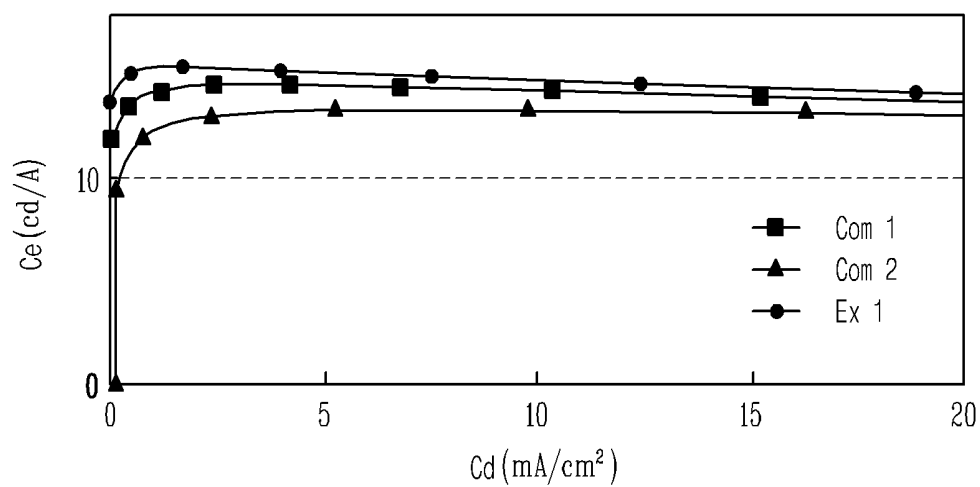
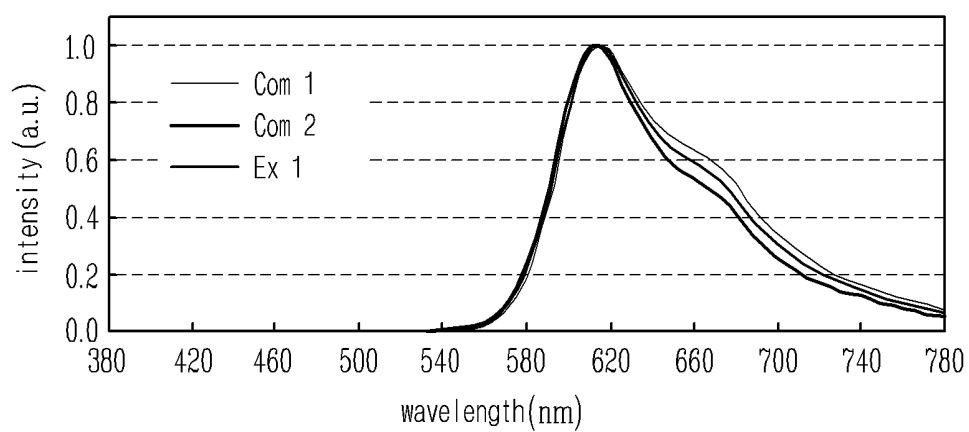
FIG. 9*FIG. 10*

FIG. 11

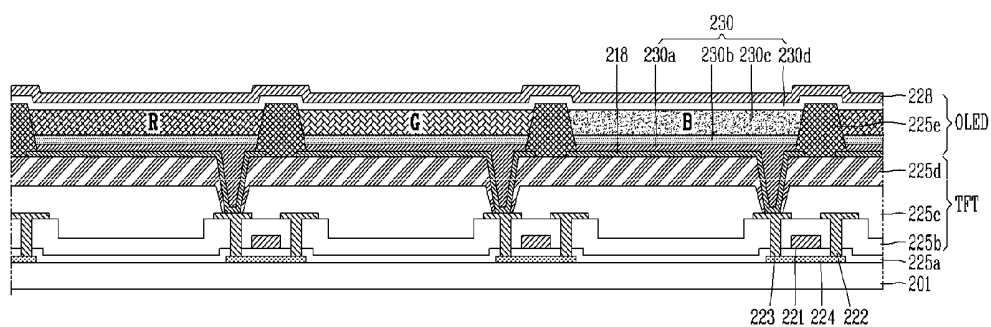


FIG. 12

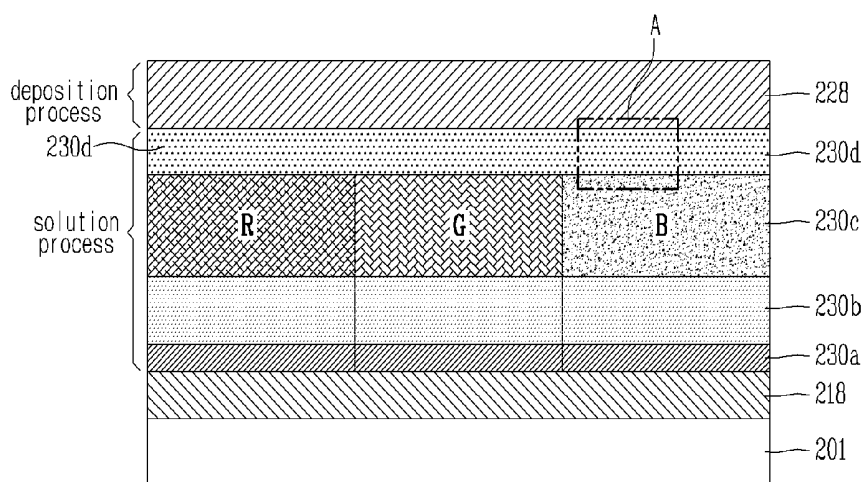


FIG. 13

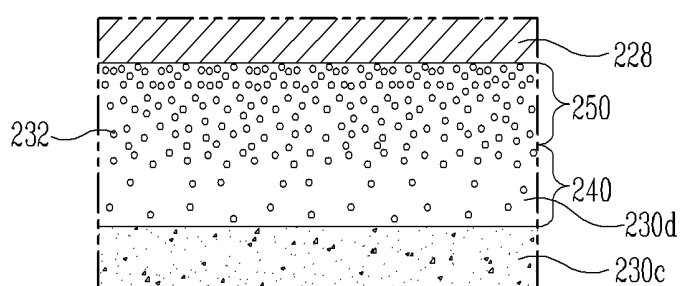
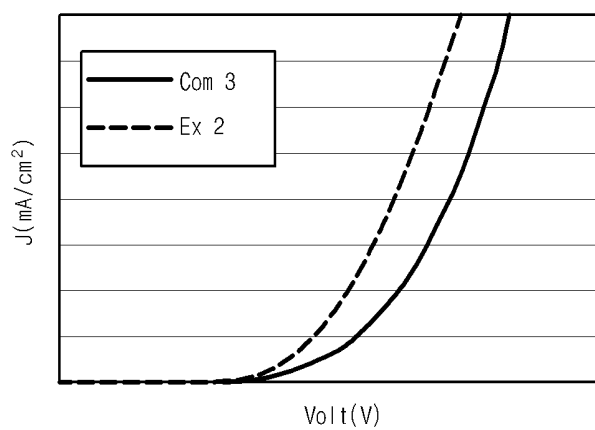


FIG. 14

V-J plot



**ORGANIC EMITTING DIODE AND
ORGANIC LIGHT EMITTING DIODE
DISPLAY DEVICE INCLUDING THE SAME**

[0001] The present application claims the benefit of Korean Patent Application No. 10-2015-0169502, filed in Korea on Nov. 30, 2015, which is hereby incorporated by reference.

BACKGROUND OF THE INVENTION

[0002] Field of the Invention

[0003] The present invention relates to an organic light emitting diode (OLED) display device, and more particularly, to an organic emitting diode and an OLED display device having an improved emitting efficiency and a simple structure.

[0004] Discussion of the Related Art

[0005] Flat panel display (FPD) devices having a light weight and a thin profile is widely researched or used instead of a cathode ray tube (CRT).

[0006] Among these FPD devices, a liquid crystal display (LCD) device has been widely used. However, the LCD device as a non-self emission type display device has disadvantages in brightness, contrast ratio and a viewing angle, the OLED display device is newly researched.

[0007] Since the OLED display device is a self-emission type display device without a backlight unit, the OLED display device has advantages in weight and thickness. In addition, the OLED display device has excellent characteristic in a viewing angle, contrast ratio, a response time, power consumption, and so on.

[0008] FIG. 1 is a diagram illustrating an emission mechanism of an OLED display device.

[0009] Referring to FIG. 1, the OLED display device includes an organic emitting diode. The organic emitting diode may include a first electrode 18 as an anode, a second electrode 28 as a cathode and first to fifth organic layers 30a, 30b, 30c, 30d and 30e between the first and second electrodes 18 and 28.

[0010] The first to fifth organic layers 30a to 30e respectively serve as a hole injection layer (HIL) 30a, a hole transporting layer (HTL) 30b, an emitting material layer (EML) 30c, an electron transporting layer (ETL) 30d and an electron injection layer (EIL) 30e.

[0011] When positive and negative voltages are respectively applied to the first and second electrodes 18 and 28, holes and electrons from the first and second electrodes 18 and 28 are transported into and combined in the EML 30c to form an exciton. The exciton is transited from an excited state into a ground state (i.e., a stable state) such that the light is emitted from the organic emitting diode.

[0012] In the OLED display device, sub-pixels including the organic emitting diode are arranged in a matrix shape, and an image is displayed by selectively controlling the sub-pixels.

[0013] The OLED display device may be classified into a passive matrix type and an active matrix type. In the active matrix type OLED display device, a thin film transistor is turned on and off to select the sub-pixel, and the emission of the sub-pixel is maintained by a voltage in a storage capacitor.

[0014] Generally, the organic emitting diode is fabricated by a deposition process. Namely, a material to be deposited is evaporated in a deposition chamber such that a target layer is deposited on a substrate.

[0015] However, in the deposition process, a size of the deposition chamber should be larger than that of the substrate. In addition, additional space is required for input/output of the substrate. Accordingly, there is a limitation in the deposition process for a large-size display device.

[0016] To overcome the limitation in the deposition process, a solution process is introduced.

[0017] FIG. 2 is a cross-sectional view of the related art organic emitting diode fabricated by a solution process.

[0018] Referring to FIG. 2, the organic emitting diode includes a first electrode 18, an emitting part 30 and a second electrode 28 stacked on a substrate 1.

[0019] The emitting part 30 includes an HTL 30b, an ETL 30d and an EML 30c therebetween. To improve the emitting efficiency, an HIL 30a is formed between the first electrode 18 and the HTL 30b, and an EIL 30e is formed between the second electrode 28 and the ETL 30d.

[0020] A part of the emitting part 30 is fabricated by a solution process to be separated in red, green and blue sub-pixels R, G and B. The HIL 30a, the HTL 30b, the EML 30c are formed by the solution process. However, since the materials of the ETL 30d and the EIL 30e have insufficient stability to the solution process, the ETL 30d and the EIL 30e are formed by a deposition process.

[0021] The ETL 30d and the EIL 30e are required to improve the emitting efficiency of the organic emitting diode by efficiently injecting and/or transporting the electron into the EML 30c.

[0022] On the other hand, the EIL 30e, which includes sodium fluoride (NaF), may be formed on the EML 30c without the ETL 30d. In this instance, the material of the EIL 30e is diffused into the EML 30c such that the electron injection is increased.

[0023] However, since a portion of the EML 30c is changed into a non-emission part by diffusion of material of the EIL 30e, a thickness of the EML 30c should be increased to be over a pre-determined thickness. As a result, the driving voltage for the organic emitting diode is increased, and there is a limitation in the solution process to increase the thickness of the EML 30c.

[0024] Namely, the Na⁺ ion of the EIL 30e is diffused into the EML 30c such that the electron transporting property is increased, while the emitting efficiency is decreased by the Na⁺ ion diffused portion of the EML 30c. To prevent the decrease of the emitting efficiency, it is required to increase the thickness of the EML 30c. However, the driving voltage for the organic emitting diode is increased by the thickness increase of the EML 30c. In addition, since the viscosity of the solution for the solution process should be increased to increase the thickness of the EML 30c, the coating property is decreased.

SUMMARY

[0025] Accordingly, the present invention is directed to an organic emitting diode and an OLED display device including the same that substantially obviate one or more of the problems due to limitations and disadvantages of the related art.

[0026] Additional features and advantages of the invention will be set forth in the description which follows, and

in part will be apparent from the description, or may be learned by practice of the invention. The objectives and other advantages of the invention will be realized and attained by the structure particularly pointed out in the written description and claims hereof as well as the appended drawings.

[0027] To achieve these and other advantages and in accordance with the purpose of the present invention, as embodied and broadly described herein, an organic emitting diode comprises a first electrode; a second electrode facing the first electrode; an emitting material layer between the first and second electrodes; and an intervening layer between the emitting material layer and the second electrode and including a base material and an electron injection material, wherein the intervening layer contacts the second electrode.

[0028] In another aspect, an organic light emitting diode display device comprises a substrate including a plurality of sub-pixels; a transistor in each sub-pixel; and an organic emitting diode positioned in each sub-pixel and connected to the transistor, the organic emitting diode including: a first electrode; a second electrode facing the first electrode; an emitting material layer between the first and second electrodes; and an intervening layer between the emitting material layer and the second electrode and including a base material and an electron injection material, wherein the intervening layer contacts the second electrode.

[0029] In another aspect, a method for manufacturing an organic emitting diode comprises forming a first electrode; forming an emitting material layer on the first electrode; forming an intervening layer including a base material and an electron injection material on the emitting material layer; and forming a second electrode on the intervening layer to contact the intervening layer, wherein the emitting material layer and the intervening layer are formed by solution process.

[0030] It is to be understood that both the foregoing general description and the following detailed description are exemplary and explanatory and are intended to provide further explanation of the invention as claimed.

BRIEF DESCRIPTION OF THE DRAWINGS

[0031] The accompanying drawings, which are included to provide a further understanding of the invention and are incorporated in and constitute a part of this specification, illustrate embodiments of the invention and together with the description serve to explain the principles of the invention.

[0032] FIG. 1 is a diagram illustrating an emission mechanism of an OLED display device.

[0033] FIG. 2 is a cross-sectional view of the related art organic emitting diode fabricated by a solution process.

[0034] FIG. 3 is a schematic block diagram illustrating an OLED display device according to the present invention.

[0035] FIG. 4 is a circuit diagram of a sub-pixel in an OLED display device according to the present invention.

[0036] FIG. 5 is a cross-sectional view of an OLED display device according to the present invention.

[0037] FIG. 6 is a cross-sectional view of an organic emitting diode according to the present invention.

[0038] FIGS. 7A and 7B are views illustrating a solution process for an organic emitting diode according to the present invention.

[0039] FIG. 8 is a graph of a current density according to a voltage in an organic emitting diode.

[0040] FIG. 9 is a graph of a current efficiency according to a current density in an organic emitting diode.

[0041] FIG. 10 is a graph of a light intensity according to a light wavelength in an organic emitting diode.

[0042] FIG. 11 is a cross-sectional view of an OLED display device according to the present invention.

[0043] FIG. 12 is a cross-sectional view of an organic emitting diode according to the present invention.

[0044] FIG. 13 is an enlarged view of portion "A" in FIG. 12.

[0045] FIG. 14 is a graph of a current density according to a voltage in an organic emitting diode.

DETAILED DESCRIPTION

[0046] In the present specification, when a first element is referred to as being "on" a second element, it can be directly on the upper surface of the second element or a third intervening element may also be present.

[0047] Reference will now be made in detail to the preferred embodiments, examples of which are illustrated in the accompanying drawings.

[0048] FIG. 3 is a schematic block diagram illustrating an OLED display device according to the present invention.

[0049] Referring to FIG. 3, the OLED display device includes an image treating unit 115, a data conversion unit 114, timing controller 113, a data driver 112, a gate driver 111 and a display panel 110.

[0050] The image treating unit 115 performs various image treating processes, e.g., setting a gamma voltage for providing a maximum brightness according to an average image level, using the RGB data signals and outputs the treated RGB data. In addition, the image treating unit 115 outputs a driving signal including at least one of a vertical sync signal (Vsync), a horizontal sync signal (Hsync), a data enable signal (DES) and a clock signal (CLK).

[0051] The timing controller 113 receives the driving signal including at least one of the Vsync, the Hsync, the DES and the CLK. The timing controller 113 outputs a gate timing control signal GCS for controlling an operation timing of the gate driver 111 and a data timing control signal DCS for controlling an operation timing of the data driver 112 according to the driving signal. In addition, the timing controller 113 outputs a data signal DATA corresponding to the GCS and the DCS.

[0052] In response to the DCS, the data driver 112 is performed a sampling process of the DATA from the timing controller 113 to output a gamma reference voltage. The data driver 112 outputs modified DATA to the data lines DL1 to DLm. The data driver 112 includes an integrated circuit (IC).

[0053] In response to the GCS from the timing controller 113, the gate driver 111 shifts a level of a gate voltage and outputs a gate signal. The gate driver 111 outputs the gate signal to the gate lines GL1 to GLn. The gate driver 111 includes an IC or is installed on the display panel 110 in a gate-in-panel (GIP) type.

[0054] The display panel 110 may include a red sub-pixel SP_r, a green sub-pixel SP_g and a blue sub-pixel SP_b. Namely, one pixel P may include the red, green and blue sub-pixels SP_r, SP_g and SP_b, but it is not limited thereto. For example, the pixel P may further include a white sub-pixel.

[0055] FIG. 4 is a circuit diagram of a sub-pixel in an OLED display device according to the present invention.

[0056] In FIG. 4, the sub-pixel includes a switching transistor, a driving transistor and a capacitor with an organic

emitting diode. Namely, the sub-pixel has a 2-transistor-1-capacitor (2T1C) structure. Alternatively, the sub-pixel may have a 3T1C structure, a 4T2C structure or a 5T2C structure.

[0057] Referring to FIG. 4, in the OLED display device, a sub-pixel region is defined by a gate line GL, a data line DL and a power line VDDL. The gate line GL extends along a first direction, and each of the data line DL and the power line VDDL extend along a second direction to cross the gate line GL. The data line DL and the power line VDDL are spaced apart from each other to be parallel to each other.

[0058] In each sub-pixel, the switching transistor SW, the driving transistor DR, the capacitor Cst, a compensation circuit CC and the organic light emitting diode OLED.

[0059] The organic emitting diode is operated to emit the light according to a driving current through the driving transistor DR. The switching transistor SW is switched to store the data signal, which is provided through the data line DL according to the gate signal provided through the data line GL, into the capacitor Cst as a data voltage. The driving transistor DR is operated to provide the signal of the power line VDDL to the ground GND according to the data voltage in the capacitor Cst. The threshold voltage of the driving transistor DR is compensated by the compensation circuit CC. For example, the compensation circuit CC may include at least one transistor and at least one capacitor, but it is not limited thereto.

[0060] The OLED display device may be classified into a top emission type, a bottom emission type or a dual emission type according to an emitting direction of the light.

[0061] FIG. 5 is a cross-sectional view of an OLED display device according to the present invention, and FIG. 6 is a cross-sectional view of an organic emitting diode according to the present invention.

[0062] In FIG. 5, one pixel includes the red, green and blue (RGB) sub-pixels. The OLED display device in FIG. 5 will be explained in the bottom emission type. Namely, the light from the organic emitting diode passes through a substrate 101 to display image. Alternatively, the light from the organic emitting diode may pass a second electrode 128 (top emission type). In addition, the light from the organic emitting diode may pass both the substrate 101 and the second electrode 128 (dual emission type).

[0063] In FIG. 5, the OLED display device includes a thin film transistor of a coplanar structure, but it is not limited thereto.

[0064] Referring to FIGS. 5 and 6, the OLED display device includes a transistor TFT on the substrate 101 and an organic emitting diode OLED over the substrate 101.

[0065] For example, the substrate 101 may be divided into the red, green and blue sub-pixels R, G and B, and the R, G and B sub-pixels may be regularly repeated in each line direction or in a diagonal direction.

[0066] The transistor TFT as a driving thin film transistor includes a semiconductor layer 124, a gate electrode 121, a source electrode 122 and a drain electrode 123.

[0067] The semiconductor layer 124 is formed on the substrate 101 being formed of an insulating material such as a transparent plastic or a transparent polymer film.

[0068] The semiconductor layer 124 may be formed of amorphous silicon, a poly-silicon, an oxide semiconductor or an organic semiconductor.

[0069] A buffer layer (not shown) may be formed between the substrate 101 and the semiconductor layer 124. The

transistor TFT is protected from impurities, e.g., alkali ion, from the substrate 101 by the buffer layer.

[0070] A gate insulating layer 125a is formed on the semiconductor layer 124. For example, the gate insulating layer 125a may be formed of an inorganic insulating material such as silicon oxide or silicon nitride. The gate electrode 121, a gate line (not shown) and a first capacitor electrode (not shown) are formed on the gate insulating layer 125a. The gate electrode 121 corresponds to the semiconductor layer 124.

[0071] Each of the gate electrode 121, the gate line and the first capacitor electrode is formed of a first metallic material having low resistance. For example, each of the gate electrode 121, the gate line and the first capacitor electrode may be formed of at least one of aluminum (Al), copper (Cu), molybdenum (Mo), chromium (Cr), gold (Au), titanium (Ti), nickel (Ni), neodymium (Nd) and their alloys and may have a single-layered structure or a multi-layered structure.

[0072] An interlayer insulating layer 125b, which is formed of an inorganic material such as silicon oxide or silicon nitride, is formed on the gate electrode 121, the gate line and the first capacitor electrode, and a data line (not shown), a power line (not shown), the source electrode 122, the drain electrode 123 and a second capacitor electrode (not shown) are formed on the interlayer insulating layer 125b.

[0073] The source and drain electrodes 122 and 123 are spaced apart from each other and electrically connected to the semiconductor layer 124, respectively. For example, first and second semiconductor contact holes are formed through the gate insulating layer 125a and the interlayer insulating layer 125b to expose both ends of the semiconductor layer 124, and the source and drain electrodes 122 and 123 contact the semiconductor layer 124 through the first and second semiconductor contact holes, respectively.

[0074] The second capacitor electrode overlaps the first capacitor electrode with the interlayer insulating layer 125b therebetween to form a storage capacitor.

[0075] Each of the data line, the power line, the source electrode 122, the drain electrode 123 and the second capacitor electrode may be formed of a second metallic material having low resistance. For example, each of the data line, the power line, the source electrode 122, the drain electrode 123 and the second capacitor electrode may be formed of at least one of Al, Cu, Mo, Cr, Au, Ti, Ni, Nd and their alloys and may have a single-layered structure or a multi-layered structure.

[0076] A passivation layer (or a planarization layer) 125c is formed over the substrate 101 including the data line, the power line, the source electrode 122, the drain electrode 123 and the second capacitor electrode, and an overcoat layer 125d is formed on the passivation layer 125c. A drain contact hole exposing the drain electrode 123 is formed through the overcoat layer 125d and the passivation layer 125c.

[0077] The passivation layer 125c may be formed of an organic material, an inorganic material or their mixture. When the passivation layer 125c has a function of the overcoat layer, the overcoat layer 125d may be omitted.

[0078] The organic emitting diode OLED including a first electrode 118, an emitting part 130 and a second electrode 128 is formed on the overcoat layer 125d.

[0079] The organic emitting diode OLED is electrically connected to the driving thin film transistor TFT. In more detail, the first electrode 118 on the overcoat layer 125d is

electrically connected to the drain electrode **123** of the driving thin film transistor TFT through the drain contact hole.

[0080] The first electrode **118** providing a current (or a voltage) to the emitting part **130** defines an emission region of a pre-determined area.

[0081] The first electrode **118** includes a relatively high work function to serve as an anode. For example, the first electrode **118** may include a transparent conductive material, e.g., indium-tin-oxide (ITO) or indium-zinc-oxide (IZO), but it is not limited thereto.

[0082] In FIG. 5, the first electrodes **118** in the R, G and B sub-pixel are separated from each other. Alternatively, the first electrodes **118** in the R, G and B sub-pixel are integrated to have one-body.

[0083] A bank **125e** is formed over the substrate **101** including the first electrode **118**. The bank **125e** covers edges of the first electrode **125e** to surround the sub-pixel. Namely, the bank **125e** has an opening in correspondence to a center of the first electrode **118**. The bank **125e** may include an organic material. The bank **125e** may be formed of a photo-sensitive material including a black pigment to serve as a light shielding element.

[0084] The emitting part **130** and the second electrode **128** are sequentially formed over the substrate **101** including the bank **125e**.

[0085] The emitting part **130** is disposed between the first and second electrodes **118** and **128**. The holes from the first electrode **118** and the electrons from the second electrode **128** are combined in the emitting part **130** such that the emitting part **130** emits.

[0086] The emitting part **130** includes an HTL **130b** as an auxiliary layer and an EML **130c** as a light emitting layer. The HTL **130b** may have a single-layered structure or a multi-layered structure. To improve the emitting efficiency, the emitting part **130** may further include an HIL **130a** between the first electrode **118** and the HTL **130b**.

[0087] The EML **130** includes a first emitting layer **130c'** having an improved interface property with the HTL **130b** and a second emitting layer **130c''** (referred to as "intervening layer" in another embodiment) having an improved electron injection property. An electron injection material is added into the emitting material of the EML **130** to form the second emitting layer **130c''**.

[0088] Namely, the first emitting layer **130c'** includes a material improving the interface property with the HTL **130b** to increase a lifetime of the organic emitting diode OLED. On the other hand, the second emitting layer **130c''** includes the emitting injection material to have an improved electron injection property such that the emitting efficiency of the organic emitting diode OLED is increased.

[0089] The electron injection material may have a concentration (or density) gradient in the second emitting layer **130c''** as explained with FIG. 13. Namely, the electron injection material in a lower portion, which is adjacent to the first emitting layer **130c'**, of the second emitting layer **130c''** may have a first concentration (or density) with respect to the emitting material in the second emitting layer **130c''**, and the electron injection material in an upper portion, which is adjacent to the second electrode **128**, of the second emitting layer **130c''** may have a second concentration (or density), which is larger than the first concentration (or density), with respect to the emitting material in the second emitting layer **130c''**.

[0090] The second emitting layer **130c''** is formed by a solution process using a solvent being damage-less to the first emitting layer **130c'**. Accordingly, since the electron injection property is improved by the second emitting layer **130c''**, the emitting efficiency of the organic emitting diode OLED is increased without the ETL and the EIL.

[0091] For example, the electron injection material may include water-soluble or fat-soluble alkali metal. When the first emitting layer **130c'** is formed using an organic solvent (i.e., fat-soluble), the second emitting layer **130c''** is formed using the water-soluble material to prevent damages on the first emitting layer **130c'**. Alternatively, when the first emitting layer **130c'** is formed using the water-soluble solvent, the second emitting layer **130c''** is formed using the organic solvent (i.e., fat-soluble solvent) to prevent damages on the first emitting layer **130c'**.

[0092] The second emitting layer **130c''** has a relatively low lowest unoccupied molecular orbital (LUMO) energy level, e.g., about 3.0 eV to 2.6 eV, and a triplet energy level (T1) of about 2.0 eV to about 2.5 eV. In addition, the second emitting layer **130c''** has an electron mobility of about 10^{-6} cm²/Vs to about 10^{-4} cm²/Vs.

[0093] In the organic emitting diode OLED of the present invention, since the electron from the second electrode **128** is securely transported into the EML **130c** without the ETL and the EIL, the OLED has sufficient emitting efficiency and lifetime with a simple structure.

[0094] Namely, the problems, which is generated by diffusion of a material in the EIL and/or ETL into the EML in the related art organic emitting diode, is prevented in the organic emitting diode OLED and the OLED display device.

[0095] The emitting part **130** is fabricated in the R, G and B sub-pixels by a solution process. Namely, a low molecular or high molecular polymer material is coated on the first electrode **130** to form the emitting part **130**.

[0096] In the emitting part **130**, the HIL **130a** may be omitted. Alternatively, the HIL **130a** and the HTL **130b** may be formed by one layer with a mixed material. In addition, at least one of the HIL **130a** and the HTL **130b** may have at least double-layered structure.

[0097] The EML **130c** in the R, G and B sub-pixels includes a fluorescent emitting material or a phosphorescent emitting material. In addition, the EML **130c** may include at least one host and at least one dopant.

[0098] The solution process for the emitting part **130** may be one of an inject printing process, a nozzle printing process, a transferring process, a thermal jet printing process a roll printing process, a gravure printing process and a spin coating process. However, it is not limited thereto.

[0099] The solution process can be performed without a mask or a chamber. Accordingly, since the solution process is simpler and the process cost is cheaper in comparison to the deposition process, the process time and the production cost for the organic emitting diode and the OLED display device are reduced.

[0100] In addition, since the ETL and the EIL, which are fabricated by the deposition process, can be omitted, the production yield of the organic emitting diode and the OLED display device is increased.

[0101] FIGS. 7A and 7B are views illustrating a solution process for an organic emitting diode according to the present invention.

[0102] FIG. 7A shows the inkjet printing process. As shown in FIG. 7A, an inkjet apparatus (not shown) including

a head **140** is disposed over the substrate **101**, and an ink is printed on the substrate **140**. The head **140** includes a jetting hole for ink jetting.

[0103] In this instance, the head **140** or the substrate **101** is moved along at least one direction during the ink jetting such that the ink **145** is selectively printed in the sub-pixels.

[0104] In the nozzle printing process, at least one nozzle having a slit shape is used to print the ink on the substrate. In comparison to the inkjet printing process, the nozzle printing process is adequate to a large size substrate. For example, a layer is printed over the substrate **101**, where the bank is formed, by an entire-surface nozzle printing process.

[0105] FIG. 7B shows the roll printing process. As shown in FIG. 7B, a main roller **150**, where a pattern **155** is formed, is rotated on the substrate **101** to form a printing pattern. In this instance, an auxiliary roller **151** is connected to a head providing a printing solution such that the printing solution is continuously provided into the pattern **155** on the main roller **150**. Without the pattern **155**, the material may be printed or coated on an entire surface of the substrate **101**.

[0106] Referring again to FIGS. 5 and 6, the second electrode **128** is formed on the emitting part **130**, and the electron is provided from the second electrode **128** into the emitting part **130**.

[0107] The second electrode **128** is formed on an entire surface of the substrate **101**. Namely, the second electrodes **128** in the sub-pixels are integrated as one-body.

[0108] FIG. 8 is a graph of a current density according to a voltage in an organic emitting diode, FIG. 9 is a graph of a current efficiency according to a current density in an organic emitting diode, and FIG. 10 is a graph of a light intensity according to a light wavelength in an organic emitting diode. The graph in FIG. 10 is obtained in the red sub-pixel.

[0109] In FIGS. 8 to 10, the organic emitting diode of the comparative example 1 (Com1) includes an electron injection layer (EIL) without an electron transporting layer (ETL), and the organic emitting diode of the comparative example 2 (Com2) includes both an EIL and an ETL.

[0110] Referring to FIG. 8, a current density (Cd) in the organic emitting diode of "Com1" is lower at the same voltage than that in the organic emitting diode of "Com2". A current density (Cd) of the organic emitting diode of the example 1 (Ex1) including the first and second emitting layers **130c'** and **130c''** without the EIL and the ETL is higher than that in the organic emitting diode of "Com1" and "Com2". Namely, the driving efficiency of the organic emitting diode of the present invention is improved, and the driving voltage of the organic emitting diode of the present invention is decreased.

[0111] Referring to FIG. 9, a current efficiency (Ce) of the organic emitting diode of the example 1 (Ex1) is higher than that in the organic emitting diode of "Com1" and "Com2". It means that the lifetime of the organic emitting diode in the present invention is increased.

[0112] Referring to FIG. 10, in the organic emitting diode of "Com1", the emitting injection material in the EIL is diffused into the EML such that an emission region is shifted. As a result, there is a peak in a wavelength above a red wavelength, i.e., 600~650 nm). However, in the organic emitting diode of "Com1" and "Ex1", the peak shift problem is reduced such that a color purity is improved.

[0113] FIG. 11 is a cross-sectional view of an OLED display device according to the present invention, and FIG.

12 is a cross-sectional view of an organic emitting diode according to the present invention.

[0114] Referring to FIGS. 11 and 12, the OLED display device includes a transistor TFT on the substrate **201** and an organic emitting diode OLED over the substrate **201**.

[0115] The substrate **201** may be divided into the red, green and blue sub-pixels R, G and B, and the R, G and B sub-pixels may be regularly repeated. For example, the substrate **201** is formed of an insulating material such as a transparent plastic or a transparent polymer film to be flexible.

[0116] The transistor TFT as a driving element includes a semiconductor layer **224**, a gate electrode **221**, a source electrode **222** and a drain electrode **223**.

[0117] The semiconductor layer **224** is formed on the substrate **201**. For example, the semiconductor layer **224** may be formed of amorphous silicon, a poly-silicon, an oxide semiconductor or an organic semiconductor.

[0118] A buffer layer (not shown) may be formed between the substrate **201** and the semiconductor layer **224**. The transistor TFT is protected from impurities, e.g., alkali ion, from the substrate **201** by the buffer layer.

[0119] A gate insulating layer **225a** is formed on the semiconductor layer **224**. For example, the gate insulating layer **225a** may be formed of an inorganic insulating material such as silicon oxide or silicon nitride.

[0120] The gate electrode **221**, a gate line (not shown) and a first capacitor electrode (not shown) are formed on the gate insulating layer **225a**. The gate electrode **221** corresponds to the semiconductor layer **224**.

[0121] Each of the gate electrode **221**, the gate line and the first capacitor electrode is formed of a first metallic material having low resistance. For example, each of the gate electrode **221**, the gate line and the first capacitor electrode may be formed of at least one of aluminum (Al), copper (Cu), molybdenum (Mo), chromium (Cr), gold (Au), titanium (Ti), nickel (Ni), neodymium (Nd) and their alloys and may have a single-layered structure or a multi-layered structure.

[0122] An interlayer insulating layer **225b** is formed on the gate electrode **221**, the gate line and the first capacitor electrode. For example, the interlayer insulating layer **225b** may be formed of an inorganic material such as silicon oxide or silicon nitride,

[0123] A data line (not shown), a power line (not shown), the source electrode **222**, the drain electrode **223** and a second capacitor electrode (not shown) are formed on the interlayer insulating layer **225b**.

[0124] The source and drain electrodes **222** and **223** are spaced apart from each other and electrically connected to the semiconductor layer **224**, respectively. For example, first and second semiconductor contact holes are formed through the gate insulating layer **225a** and the interlayer insulating layer **225b** to expose both ends of the semiconductor layer **224**, and the source and drain electrodes **222** and **223** contact the semiconductor layer **224** through the first and second semiconductor contact holes, respectively.

[0125] The second capacitor electrode overlaps the first capacitor electrode with the interlayer insulating layer **225b** therebetween to form a storage capacitor.

[0126] Each of the data line, the power line, the source electrode **222**, the drain electrode **223** and the second capacitor electrode may be formed of a second metallic material having low resistance. For example, each of the data line, the power line, the source electrode **222**, the drain

electrode **223** and the second capacitor electrode may be formed of at least one of Al, Cu, Mo, Cr, Au, Ti, Ni, Nd and their alloys and may have a single-layered structure or a multi-layered structure.

[0127] Although not shown, a switching element, which has substantially the same structure as the transistor TFT, is further formed in the R, G and B sub-pixels. The switching element is electrically connected to the gate line, the data line and the transistor TFT.

[0128] A passivation layer (or a planarization layer) **225c** is formed over the substrate **201** including the data line, the power line, the source electrode **222**, the drain electrode **223** and the second capacitor electrode, and an overcoat layer **225d** is formed on the passivation layer **225c**. A drain contact hole exposing the drain electrode **223** is formed through the overcoat layer **225d** and the passivation layer **225c**.

[0129] Each of the passivation layer **225c** and the overcoat layer **22d** is formed of an inorganic insulating material, e.g., silicon oxide or silicon nitride, or an organic insulating material, e.g., photo-acryl. One of the passivation layer **225c** and the overcoat layer **22d** may be omitted.

[0130] The organic emitting diode OLED including a first electrode **218**, an emitting part **230** and a second electrode **228** is formed on the overcoat layer **225d**. The organic emitting diode OLED is electrically connected to the transistor TFT.

[0131] The first electrode **218** is formed on the overcoat layer **225d** to be separated in the R, G and B sub-pixel and is electrically connected to the drain electrode **223** of the transistor TFT through the drain contact hole.

[0132] The first electrode **218** providing a current (or a voltage) to the emitting part **230** defines an emission region of a pre-determined area.

[0133] The first electrode **218** includes a relatively high work function to serve as an anode. For example, the first electrode **218** may include a transparent conductive material, e.g., indium-tin-oxide (ITO) or indium-zinc-oxide (IZO), but it is not limited thereto.

[0134] In the top emission type OLED display device, a reflection electrode or a reflection layer may be formed under and/or on the first electrode **218**. For example, each of the reflection electrode or the reflection layer may include aluminum-palladium-copper (APC) alloy. In other words, the first electrode **218** may have a double-layered structure including the transparent conductive electrode and the reflection electrode or layer under the transparent conductive electrode or a triple-layered structure including the transparent conductive electrode and the reflection electrode or layer under and the transparent conductive electrode.

[0135] A bank **225e** is formed over the substrate **201** including the first electrode **218**. The bank **225e** covers edges of the first electrode **225e** to surround the sub-pixel. Namely, the bank **225e** has an opening in correspondence to a center of the first electrode **218**. The bank **225e** may include an organic material. The bank **225e** may be formed of a photo-sensitive material including a black pigment to serve as a light shielding element.

[0136] The emitting part **230** and the second electrode **228** are sequentially formed over the substrate **201** including the bank **225e**.

[0137] The emitting part **230** is disposed between the first and second electrodes **218** and **228**. The holes from the first

electrode **218** and the electrons from the second electrode **228** are combined in the emitting part **230** such that the emitting part **230** emits.

[0138] The emitting part **230** includes an EML **230c** and an ETL **230d** between the EML **230** and the second electrode **228** without an electron injection layer. Namely, the ETL **230d** contacts the second electrode **228**. In addition, the emitting part **230** may further include an HIL **230a** and an HTL **230b** sequentially stacked on the first electrode **218** and under the EML **230c**.

[0139] The ETL **230d** (referred to as “intervening layer” in another embodiment) includes an electron transporting material (not shown) and an electron injection material **232** (of FIG. 13) having an excellent electron property. In other words, the electron injection material **232** is doped into the ETL **230d**.

[0140] The electron transporting material has a LUMO energy level of about 3.0 eV to about 2.0 eV and an electron mobility of about 10^{-5} cm²/Vs to about 10^{-3} cm²/Vs. In addition, the ETL **230d**, where the electron injection material **232** is doped, has a triplet energy (T1) level of about 2.0 eV to about 2.5 eV. For example, the electron injection material **232** may include water-soluble or fat-soluble alkali metal.

[0141] When the emitting material layer **230c'** is formed using an organic solvent (i.e., fat-soluble), the electron transporting layer **230d** is formed using the water-soluble material to prevent damages on the emitting material layer **230c'**. Alternatively, when the emitting material layer **230c'** is formed using the water-soluble solvent, the electron transporting layer **230d** is formed using the organic solvent (i.e., fat-soluble solvent) to prevent damages on the emitting material layer **230c'**.

[0142] The electron injection material **232** has a concentration gradient (or a density gradient) in a vertical direction.

[0143] Namely, referring to FIG. 13, which an enlarged view of a portion “A” in FIG. 12, the electron injection material **232** has a first concentration (or a first density) in a lower portion **240**, which is adjacent to the EML **230c**, of the ETL **230d** and a second concentration (or a second density) in an upper portion **250**, which is adjacent to the second electrode **228**, of the ETL **230d**. The second concentration is larger than the first concentration.

[0144] For example, the electron injection material **232** has a first weight % of about 150 in the upper portion with respect to the electron transporting material and a second weight % of about 50 in the lower portion with respect to the electron transporting material.

[0145] In addition, the electron injection material **232** may have a concentration gradient in each of the lower and upper portions **240** and **250**. Namely, in each of the lower and upper portions **240** and **250**, the concentration (or the density) of the electron injection material **232** is reduced in a direction from the upper portion **250** to the lower portion **240**. Alternatively, the electron injection material **232** may have the same concentration (or the density) in each of the lower and upper portions **240** and **250**.

[0146] The ETL **230d** includes the electron injection material **232** such that the electron injection property of the ETL **230d** is increased. Accordingly, without the EIL, the organic emitting diode has a simple structure and a thin profile.

[0147] In addition, since the electron injection material **232** has the concentration gradient in the ETL **230d**, the diffusion of the electron injection material **232** into the EML **230c** is minimized.

[0148] To provide a desired electron injection property in the ETL **230d**, the electron injection material **232** should be doped into the ETL **230d** in a pre-determined concentration. In the organic emitting diode of the present invention, since the electron injection material **232** has a relatively low concentration in the lower portion **240**, which is adjacent to the EML **230c**, of the ETL **230d**, the diffusion of the electron injection material **232** into the EML **230c** is minimized. With the first concentration (>0) of the electron injection material **232** in the lower portion **240** of the ETL **230d**, there is an advantage in the emitting efficiency by the electron injection material but there is no disadvantage in the emitting property by the diffusion of the electron injection material **232** into the EML **230c**.

[0149] In other words, in the organic emitting diode of the present invention, the electron injection property of the ETL **230d** is increased by doping the electron injection material, and the problem in the lifetime and the emitting efficiency is prevented by the concentration gradient of the electron injection material **232**.

[0150] An ITO layer and an electron blocking layer (Liq, 1 nm) are sequentially deposited on a glass substrate, and an electron transporting layer (50 nm), where an electron injection material is doped in gradient, and a cathode (Al, 100 nm) are sequentially stacked on the electron blocking layer (example 2 (Ex2), electron only device).

[0151] An ITO layer and an electron blocking layer (Liq, 1 nm) are sequentially deposited on a glass substrate, and an electron transporting layer (50 nm) without an electron injection material and a cathode (Al, 100 nm) are sequentially stacked on the electron blocking layer (comparative example 3 (Com3), electron only device).

[0152] As shown in FIG. 14, which is a graph of a current density according to a voltage in an organic emitting diode, the current density in the organic emitting diode of "Ex2", where the electron injection material is doped into the electron transporting layer to have a concentration gradient, is higher than that in the organic emitting diode of "Com3". Namely, the emitting efficiency of the organic emitting diode and the OLED display device is improved.

[0153] It will be apparent to those skilled in the art that various modifications and variations can be made in the present invention without departing from the spirit or scope of the invention. Thus, it is intended that the present invention cover the modifications and variations of this invention provided they come within the scope of the appended claims and their equivalents.

What is claimed is:

1. An organic emitting diode, comprising:

a first electrode;

a second electrode facing the first electrode;

an emitting material layer between the first and second electrodes; and

an intervening layer between the emitting material layer and the second electrode and including a base material and an electron injection material,

wherein the intervening layer contacts the second electrode.

2. The organic emitting diode according to claim 1, wherein the base material is a host material of the emitting material layer.

3. The organic emitting diode according to claim 2, wherein the intervening layer has a LUMO energy level of about 3.0 eV to 2.6 eV and a triplet energy level of about 2.0 eV to about 2.5 eV.

4. The organic emitting diode according to claim 2, wherein the intervening layer has an electron mobility of about 10^{-6} cm²/Vs to about 10^{-4} cm²/Vs.

5. The organic emitting diode according to claim 1, wherein the base material is an electron transporting material.

6. The organic emitting diode according to claim 5, wherein the electron transporting material has a LUMO energy level of about 3.0 eV to 2.0 eV and the electron transporting layer has a triplet energy level of about 2.0 eV to about 2.5 eV.

7. The organic emitting diode according to claim 5, wherein the electron transporting material has an electron mobility of about 10^{-5} cm²/Vs to about 10^{-3} cm²/Vs.

8. The organic emitting diode according to claim 1, wherein the electron injection material has a first density in a lower portion, which is adjacent to the emitting material layer, of the intervening layer and a second density, which is larger than the first density, in an upper portion, which is adjacent to the second electrode, of the intervening layer.

9. The organic emitting diode according to claim 1, wherein the electron injection material includes an alkali metal.

10. An organic light emitting diode display device, comprising:

a substrate including a plurality of sub-pixels;

a transistor in each sub-pixel; and

an organic emitting diode positioned in each sub-pixel and connected to the transistor, the organic emitting diode including:

a first electrode;

a second electrode facing the first electrode;

an emitting material layer between the first and second electrodes; and

an intervening layer between the emitting material layer and the second electrode and including a base material and an electron injection material,

wherein the intervening layer contacts the second electrode.

11. The organic light emitting diode display device according to claim 10, wherein the base material is a host material of the emitting material layer.

12. The organic light emitting diode display device according to claim 11, wherein the intervening layer has a LUMO energy level of about 3.0 eV to 2.6 eV and a triplet energy level of about 2.0 eV to about 2.5 eV.

13. The organic light emitting diode display device according to claim 11, wherein the intervening layer has an electron mobility of about 10^{-6} cm²/Vs to about 10^{-4} cm²/Vs.

14. The organic light emitting diode display device according to claim 10, wherein the base material is an electron transporting material.

15. The organic light emitting diode display device according to claim 14, wherein the electron transporting material has a LUMO energy level of about 3.0 eV to 2.0 eV

and the electron transporting layer has a triplet energy level of about 2.0 eV to about 2.5 eV.

16. The organic light emitting diode display device according to claim **14**, wherein the electron transporting material has an electron mobility of about 10^{-5} cm²/Vs to about 10^{-3} cm²/Vs.

17. The organic light emitting diode display device according to claim **10**, wherein the electron injection material has a first density in a lower portion, which is adjacent to the emitting material layer, of the intervening layer and a second density, which is larger than the first density, in an upper portion, which is adjacent to the second electrode, of the intervening layer.

18. The organic light emitting diode display device according to claim **10**, wherein the electron injection material includes an alkali metal.

19. A method for manufacturing an organic emitting diode, comprising:

- forming a first electrode;
- forming an emitting material layer on the first electrode;
- forming an intervening layer including a base material and an electron injection material on the emitting material layer; and

forming a second electrode on the intervening layer to contact the intervening layer,

wherein the emitting material layer and the intervening layer are formed by solution process.

20. The method according to claim **19**, wherein the base material is a host material of the emitting material layer or an electron transporting material.

21. The method according to claim **20**, wherein the solution process includes an inject printing process, a nozzle printing process, a transferring process, a thermal jet printing process, a roll printing process, a gravure printing process and a spin coating process.

22. The method according to claim **20**, wherein the emitting material layer is formed using an organic solvent; and the intervening layer is formed using a water-soluble material in which a water-soluble or fat soluble alkali metal as the electron injection material is dispersed.

23. The method according to claim **20**, wherein the emitting material layer is formed using a water-soluble material; and the intervening layer is formed using an organic solvent in which a water-soluble or fat soluble alkali metal as the electron injection material is dispersed.

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摘要(译)

本发明提供一种有机发光二极管，包括第一电极;面向第一电极的第二电极;第一和第二电极之间的发光材料层;发光材料层和第二电极之间的中间层，包括基底材料和电子注入材料，其中，中间层与第二电极接触。

